	Application No.	Applicant(s)	Applicant(s)	
Notice of Allowability	10/632,636	DURHAM ET AL.		
	Examiner	Art Unit	1	
	Lisa Kilday	2829	And	
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.				
1. X This communication is responsive to 8/4/03.				
2. 🔀 The allowed claim(s) is/are <u>29-43</u> .				
3. 🔀 The drawings filed on <u>04 August 2003</u> are accepted by the Examiner.				
4. Acknowledgment is made of a claim for foreign priority un a) All b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)). * Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE"	been received. been received in Application cuments have been received	on No ed in this national stage applica		
noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 5. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give	itted. Note the attached EX		OTICE OF	
 6. CORRECTED DRAWINGS (as "replacement sheets") must be submitted. (a) including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached 1) hereto or 2) to Paper No./Mail Date (b) including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the drawings in the front (not the back) of each sheet. Replacement sheet(s) should be labeled as such in the header according to 37 CFR 1.121(d). 7. DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL. 				
 Attachment(s) 1. ☑ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date	6. ☐ Interview 9 Paper No 8), 7. ⊠ Examiner's	nformal Patent Application (PTC Summary (PTO-413), ./Mail Date s Amendment/Comment s Statement of Reasons for Allo 		

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EXAMINER'S AMENDMENT

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Kevin Jackson and Bruce Huling on 8/19/04.

The application has been amended as follows:

On pg. 4, line 33 change typographical error from: "contiguous?" to -continuous-

Amend claim 29: A method of making a semiconductor structure, comprising the steps of: oxidizing sidewalls of cavities in a semiconductor material to form a continuous oxide layer between adjacent cavities, thereby forming a pillar of the semiconductor material; and etching the continuous oxide layer between said adjacent cavities.

The following is an examiner's statement of reasons for allowance: In re claims 29-30, Tsou (5,240,875) teaches a method of oxidizing sidewalls of cavities in a semiconductor material in order to form a pillar. However, prior art does not teach or suggest forming a continuous oxide layer between adjacent cavities during the oxidation and growth step of the semiconductor material.

In re claims 31-43, Tsou teaches forming a pillar with a semiconductor material below a surface of a substrate. However, prior art does not teach or suggest limitation of

Application/Control Number: 10/632,636 Page 3

Art Unit: 2829

forming a void by capping the pillar with a first dielectric material in *combination with* forming an electrical component over the void.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

Any inquiry of a general nature or relating to the status of this application should be directed to the Group Receptionist whose telephone number is (703) 308-0957. See MPEP 203.08.

Any inquiry concerning this communication from the examiner should be directed to Lisa Kilday whose telephone number is (571) 272-1962. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Michael Tokar, can be reached on (571) 272-1812. The fax number for the group is (703) 872-9306. MPEP 502.01 contains instructions regarding procedures used in submitting responses by facsimile transmission.

Lisa Kilday

LAK

8/19/04

Michael Tokar Supervisory Patent Examiner Technology Center 2800

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